Ref #	Hits	Search Query	DBs	Default Operato r	Plural s	Time Stamp
L1	357963	(plasma cvd ALD (atomic near5 layer near5 deposit\$3) (chemical near5 vapor near5 deposit\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 12:05
L2	24311	1 and (BPSG PSG (borophosphosilicate near5 glass) (dop\$3 near5 silicon near5 (oxide dioxide)))	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 12:05
L3	1158	2 and (phosphorus near5 dop\$3 near5 silicon near5 (oxide dioxide))	US-PGPU B; USPAT; USOCR	OR	ON .	2005/07/05 12:06
L4	0	3 and ("Si" near3 "OR"".sub. 3" near3 "OH")	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:54
L5	810	("PO" near5 "OR")	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:56
L6	269	("Si" near5 "OR" near5 "OH")	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:56
L7	9	5 and 6	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:57
L8	402	("PO" near5 "O" near5 "CH")	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:58
L9	85	("Si" near5 "O" near5 "CH" near5 "OH")	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:58
L10	0	8 and 9	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:59
L11	487	8 9	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:59
L12	0	3 and 11	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 11:59
L13	29461	hydrocarbyl hydro-carbyl	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 12:00
L14	5	13 and 3	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 12:00

Ref #	Hits	Search Query	DBs	Default Operato r	Plural s	Time Stamp
L2	3142	chemisorb\$3	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 17:44
L3	2835	2 and (silicon (oxide dioxide))	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 17:44
L4	503	3 and phosphorus	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 17:45
L5	215	4 and (pulse cvd plasma (chemical near5 vapor near5 deposit\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 16:23
L 7	215	4 and (pulse cvd ALD (atomic near5 layer near5 deposit\$3) plasma (chemical near5 vapor near5 deposit\$3))	US-PGPU B; USPAT; USOCR	OR	ON	2005/07/05 16:24
L8	420	chemisorb\$3	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/05 17:44
L9	130	8 and (silicon (oxide dioxide))	EPO; JPO; DERWENT	OR	ON	2005/07/05 17:44
		,	IBM_TDB			
L10	3	9 and phosphorus	EPO; JPO; DERWENT	OR	ON	2005/07/05 17:45
			; IBM_TDB			

L15	232980	(plasma cvd ALD (atomic near5 layer near5 deposit\$3) (chemical near5 vapor near5 deposit\$3))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/05 12:05
L16	2074	15 and (BPSG PSG (borophosphosilicate near5 glass) (dop\$3 near5 silicon near5 (oxide dioxide)))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/05 12:06
L17	38	16 and (phosphorus near5 dop\$3 near5 silicon near5 (oxide dioxide))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/07/05 12:06